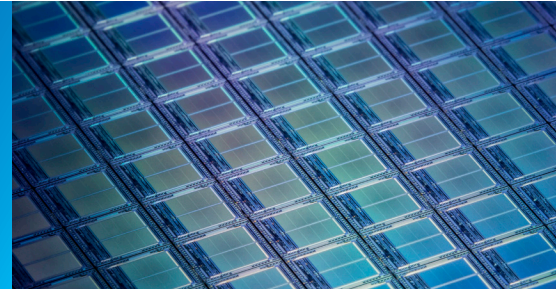


# Archer™ 800

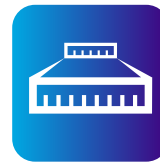
Imaging-Based Overlay Metrology System



The Archer™ 800 overlay metrology system provides accurate feedback of on-product overlay error for fast technology ramps and stable production of leading-edge memory and logic devices.



Accurate



Extended  
Measurability

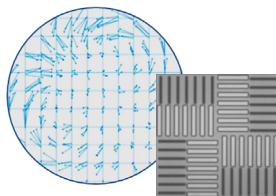
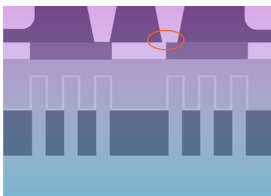


Robust

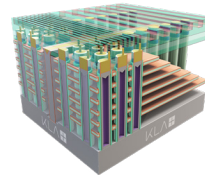


Fast

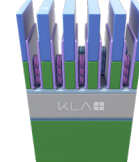
**Overlay metrology** tool measures alignment of the pattern of features between process layers.



**Advanced ICs:** Supports R&D, fast ramp and stable production of leading-edge devices.



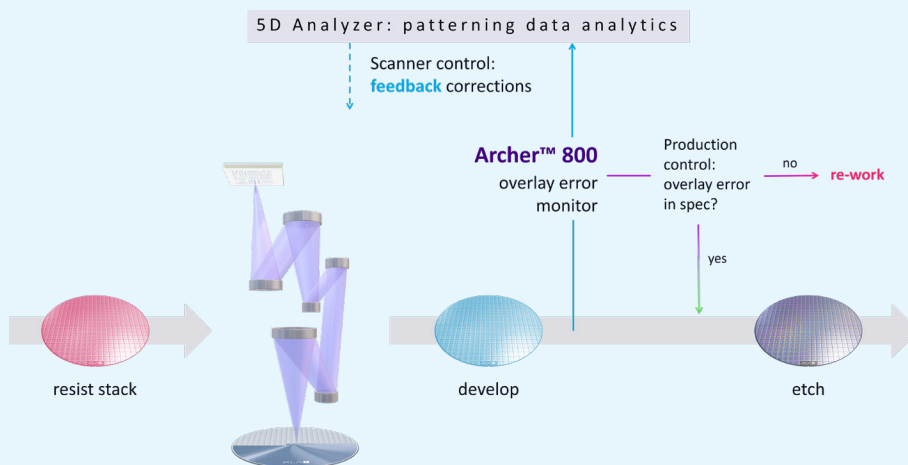
3D NAND



Logic



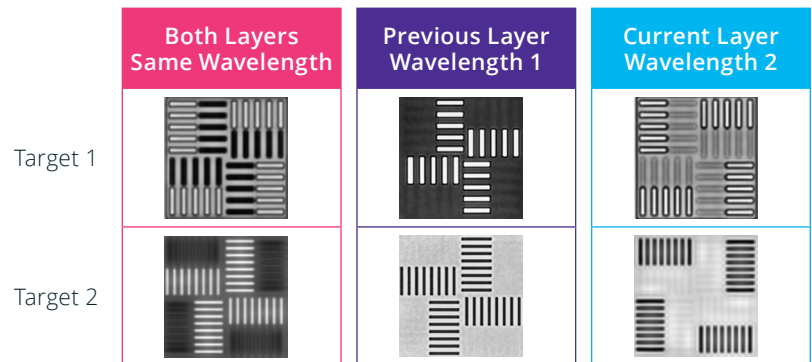
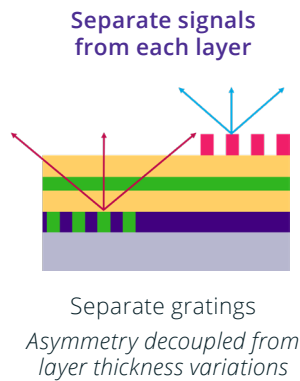
DRAM



**Archer overlay metrology systems** produce data that enable lithographers to identify excursions and improve On Product Overlay (OPO) control.

## Optimized Conditions Per Layer

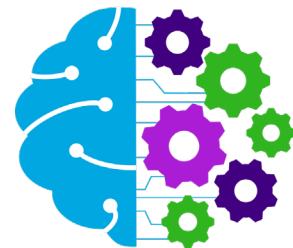
Parallel Color per Layer (PCPL) and Focus Per Layer (FPL) measurement modes enhance target signal-to-noise for accurate overlay measurements on challenging lithography stacks, EUV thin resists and opaque films.



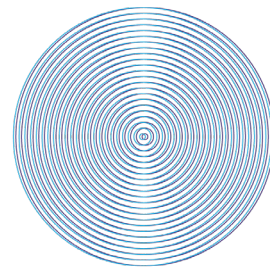
## Supporting Capabilities

### Deep Learning and Machine Learning Algorithms

- mTIS (Model TIS) produces calibrated overlay for best measurement performance (accuracy, TMU, matching).
- mFocus supports robust and fast measurement sequences.



**rAIM®** provides improved device to target correlation and better process robustness for improved OPO.



**Multi-signal measurement mode** provides robustness to process variation via affluent and accurate overlay target asymmetry information.



### KLA SERVICES

From tool installation and system optimization to productivity enhancements and global supply chain management, KLA Services is a trusted partner to customers around the world — delivering an unrivaled experience focused on maximizing tool performance and availability.

KLA Corporation  
www.kla.com

Rev 1.4\_05-16-2025